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ABSTRACT OF THE INVENTION

Vortex phase shift mask for optical lithography

A photolithography method and apparatus for producing minima of light intensity corresponding to a point in a phase shift mask is described. The phase shift in the light produced by the mask varies in a spiral fashion around the point so that the phase shift measured along lines drawn across the surface of the mask which pass through the point have a 180° jump at the point, and lines passing around the point have no jumps between 130° and 230°, and most preferably no jumps between 100° and 260°.

Figure 2